

**RESPONSE UNDER 37 CFR §1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 1794**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	Atty. Docket : NL 021426
RALPH KURT ET AL.	Group Art Unit: 1794
Serial No. 10/539,362	Examiner: ELIZABETH E. MULVANEY
Filed: JUNE 15, 2005	CONF. NO. 7350

TITLE: USE OF BI-LAYER PHOTOLITHOGRAPHIC RESISTS AS NEW MATERIAL
FOR OPTICAL STORAGE

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT AFTER FINAL ACTION UNDER 37 C.F.R. §1.116

Sir:

In response to the Final Office Action of July 25, 2008,
please amend the application and consider the remarks as follows: